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Introduction

The methods of optical metrology have advanced significantly since the times of the early interferometers of the late 19th century. Fast cameras and processing make a whole range of new methods available today for looking at everything from fine microstructures to large astronomical systems. The papers presented in this conference focused on optical methods beyond traditional white-light or monochromatic-laser interferometric methods to other optical means of making precision measurements. They discuss novel uses of polarization, pattern projection, deflectometry spectroscopy, and other means to measure everything from fine semiconductor structures to aircraft components to subway tunnel geometry. We hope you enjoy the novel ways in which optical metrology is enabling various new applications and industries.

Erik Novak
James D. Trolinger